



09/927,102

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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor Patent Application of

Michael Weber-Grabau, et al.

Application No.: 09/927,102

Filed: August 10, 2001

For: CRITICAL DIMENSION
METROLOGY SYSTEM
INTEGRATED INTO
SEMICONDUCTOR WAFER
PROCESS TOOL

Confirmation No.: 3815

Group Art Unit: 2877

Examiner: Richard A. Rosenberger

**RESPONSE TO FINAL REJECTION
MAILED JUNE 28, 2006**

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Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope, addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on September 27, 2006.

STALLMAN & POLLOCK LLP

Dated: 09/ 7/2006

By: 

Lana T. Brenner

Sir:

In response to the Office Action mailed June 28, 2006, and in conjunction with the Request for Continued Examination filed herewith, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the Listing of Claims that begins on page 2 of this paper.

Remarks begin on page 7 of this paper.